

ABSTRACT OF THE DISCLOSURE

The invention provides a substrate processing apparatus including a processing tank for processing substrates, a transporting path provided along the processing tank, a substrate transporting device moving along the transporting path for transporting the substrates, wherein the substrate processing apparatus and the substrate transporting device mounted thereto may realize the improvement of the throughput of substrate processing without increasing the area for installing the substrate processing apparatus. There are provided at least two substrate transporting devices that are capable of moving on the identical transporting path. The movable ranges of the respective substrate transporting devices for transporting the substrates are overlapped with respect to each other. When transportation of the substrates is required simultaneously at a plurality of processing tanks in scheduling data prepared by a scheduler, the scheduling data is determined by referencing substrate transportation sharing conditions.